



Systems And Methods For Undermedia Repellency

[View U.S. Patent No. 11,951,472 in PDF format.](#)

WARF: P170307US02

Inventors: David Beebe, Chao Li, Jiaquan Yu, Theodorus de Groot

The Invention

Systems, methods, compositions of matter, and kits for undermedia repellency are disclosed. In some cases, these involve a first volume of a first liquid presented in a second volume of a second liquid above a first location of a first surface. The first liquid, second liquid, and first location can have properties sufficient to give rise to undermedia perfect liquid repellency.

Additional Information

For More Information About the Inventors

- [David Beebe](#)

Tech Fields

- [Analytical Instrumentation, Methods & Materials : Microfluidics](#)

For current licensing status, please contact Jeanine Burmania at jeanine@warf.org or 608-960-9846